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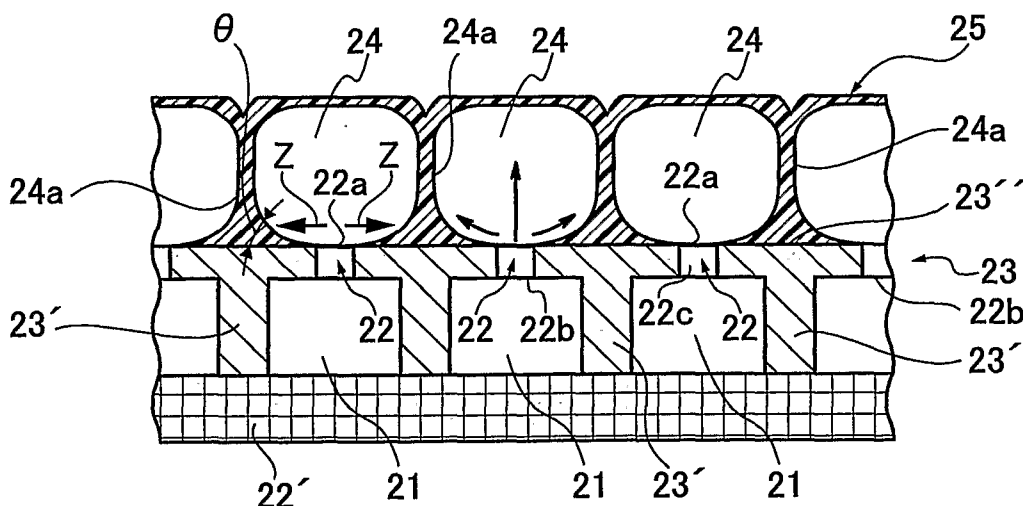
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(54) Title: HOLLOW STRUCTURE FORMING SUBSTRATE, METHOD OF PRODUCING THE SAME, AND METHOD OF PRODUCING HOLLOW STRUCTURE USING THE SAME



(57) Abstract: A hollow structure forming substrate includes: a surface (23") on which a plastic-deformation film (24) is formed by using a plastic-deformable material; a plurality of regularly-arranged gas-retaining spaces (21); a plurality of gas leading-out parts (22) each having a first opening (22b) which faces corresponding one of the gas-retaining spaces (21) and a second opening (22a) which faces the surface (23"), the gas leading-out parts leads out gas retained in the gas-retaining spaces (22) toward the surface (23") under depressurized environmental condition; and a plurality of infiltration preventing spaces (22c) each provided in a space between corresponding one of the first openings (22b) and corresponding one of the second openings (22a), in which the infiltration preventing spaces (22c) prevent infiltration of the plastic-deformable material from the surface (23") into the gas-retaining spaces (22c).

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